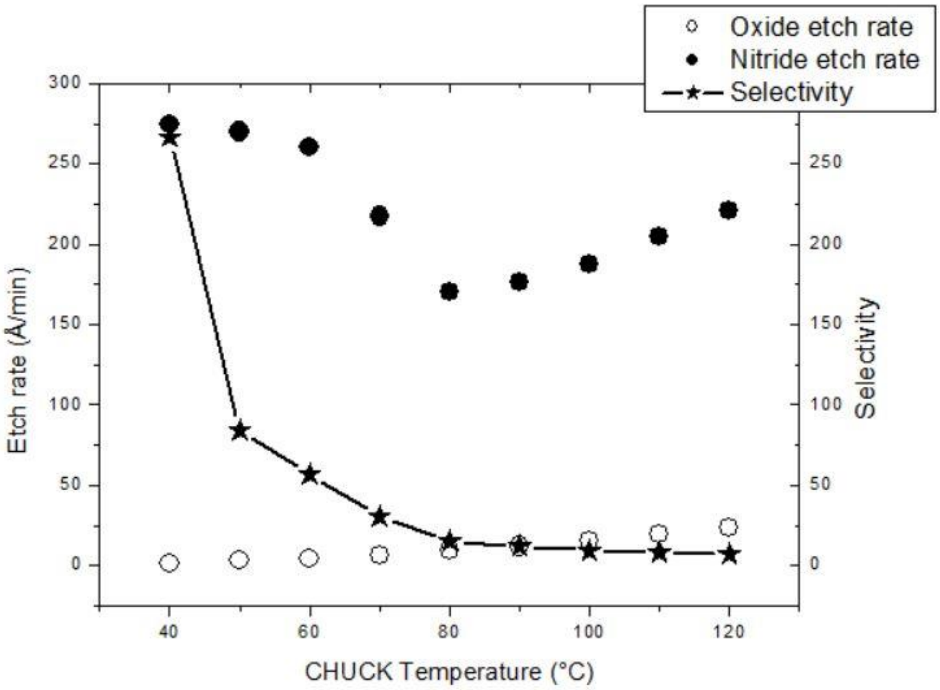
Etch rate of silicon nitride and silicon oxide (corresponding selectivity) depending of the temperature



Angular Resolved XPS: chemical composition normalized depending on the surface depth and temperature